

INFORMATION DISCLOSURE CITATION
(Use several sheets if necessary)

Docket Number (Optional)

FIS9-2001-

Application Number

10/014,707

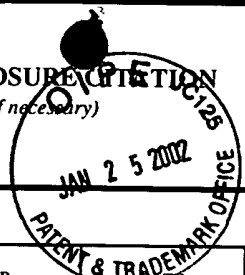
Applicant(s)

LIEBMANN ET AL.

Filing Date

11-13-01

Group Art Unit



U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
BB		6,251,564	06-26-01	LIN ET AL.			
BB		5,895,735	04-20-99	YOON			
BB		5,717,218	02-10-98	COUFAL ET AL.			
BB		5,565,286	10-15-96	LIN			
BB		5,526,183	06-11-96	CHEN			
BB		5,472,814	12-05-95	LIN			
BB		5,432,044	07-11-95	SHIMIZU			
BB		5,429,896	07-04-95	HASEGAWA ET AL.			
BB		5,403,682	04-04-95	LIN			
BB		5,364,716	11-15-94	NAKAGAWA ET AL.			
BB		5,308,741	05-03-94	KEMP			

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation
							YES NO
BB		8-211590	05-22-96	JAPAN			
BB		0 713 142 A2	05-22-96	EP			
BB		6- 95353	04-08-94	JAPAN			

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

BB		NEW GRAPH BIPARTIZATIONS FOR DOUBLE-EXPOSURE, BRIGHT FIELD ALTERNATING PHASE-SHIFT MASK LAYOUT, ANDREW B. KAHNG, SHAILESH VAYA, AND ALEXANDER ZELIKOVSKY, IEEE, 2001, pp. 133-138

EXAMINER

Barbara Bowen

DATE CONSIDERED

9/15/07

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.